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Attorney Docket: 381AS/50311TR  
PATENT



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: SHUICHI KANNO ET AL.

Serial No.: 09/005,006      Group Art Unit: 1754

Filed: JANUARY 9, 1998      Examiner: N. NGUYEN

Title: PROCESS FOR TREATING FLUORINE COMPOUND-  
CONTAINING GAS

AMENDMENT

Commissioner for Patents  
Washington, D.C. 20231

Sir:

The following amendments and remarks are respectfully  
submitted in response to the Office Action mailed March 13,  
2001.

IN THE CLAIMS:

Please amend Claim 24 as follows:

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24. (Amended) A process for treating a fluorine compound-  
containing gas, which comprises contacting a gas stream  
containing at least one of compounds consisting of carbon and  
fluorine, compounds consisting of carbon, hydrogen and  
fluorine, and compounds consisting of carbon, hydrogen, oxygen  
and fluorine with a catalyst comprising aluminum and nickel as  
metallic components in the form of single oxides or composite  
oxides and showing a decomposition activity to carry out a  
reaction with steam or a reaction gas comprising steam and  
oxygen at a reaction temperature of 400° to 800°C, thereby  
decomposing the fluorine compound to hydrogen fluoride and  
carbon dioxide.

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